

ABSTRACT

An object of the invention is to provide a polishing pad capable of maintaining a high level of dimensional stability during absorption of moisture or water and to provide a method for manufacturing such a polishing pad. The invention is related to a polishing pad including a polishing layer including a polyurethane foam having fine cells, wherein the polyurethane foam includes a cured product of a reaction of an isocyanate-terminated prepolymer (A), a polymerized diisocyanate, and a chain extender, and the isocyanate-terminated prepolymer (A) includes an isocyanate monomer, a high molecular weight polyol (a), and a low molecular weight polyol.